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Substitute for form 1449A/PTO			<p align="center"><i>Complete if Known</i></p> <p>Application Number: 10/055,560 Filing Date: 01-22-2002 First Named Inventor: MOU-SHIUNG LIN Art Unit: 2813 Examiner Name: JAMES M. MITCHELL</p>		
<p align="center">INFORMATION DISCLOSURE STATEMENT BY APPLICANT</p> <p align="center"><i>(Use as many sheets as necessary)</i></p>					
Sheet	1	of	3	Attorney Docket No: 085027-0058	

US PATENT DOCUMENTS					
Examiner Initial *	Cite No	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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FOREIGN PATENT DOCUMENTS						
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		NONE				

OTHER DOCUMENTS -- NON PATENT LITERATURE DOCUMENTS				
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	1	MISTRY, K. et al. "A 45nm Logic Technology with High-k+ Metal Gate Transistors, Strained Silicon, 9 Cu Interconnect Layers, 193nm Dry Patterning, and 100% Pb-free Packaging," IEEE International Electron Devices Meeting (2007) pgs. 247-250		
	2	EDELSTEIN, D.C., "Advantages of Copper Interconnects," Proceedings of the 12th International IEEE VLSI Multilevel Interconnection Conference (1995) pgs. 301-307		
	3	THENG, C. et al. "An Automated Tool Deployment for ESD (Electro-Static-Discharge) Correct-by-Construction Strategy in 90 nm Process," IEEE International Conference on Semiconductor Electronics (2004) pgs. 61-67		
	4	GAO, X. et al. "An improved electrostatic discharge protection structure for reducing triggering voltage and parasitic capacitance," Solid-State Electronics, 27 (2003), pgs. 1105-1110		
	5	YEOH, A. et al. "Copper Die Bumps (First Level Interconnect) and Low-K Dielectrics in 65nm High Volume Manufacturing," Electronic Components and Technology Conference (2006) pgs. 1611-1615		
	6	HU, C-K. et al. "Copper-Polyimide Wiring Technology for VLSI Circuits," Materials Research Society Symposium Proceedings VLSI V (1990) pgs. 369-373		
	7	ROESCH, W. et al. "Cycling copper flip chip interconnects," Microelectronics Reliability, 44 (2004) pgs. 1047-1054		
	8	LEE, Y-H. et al. "Effect of ESD Layout on the Assembly Yield and Reliability," International Electron Devices Meeting (2006) pgs. 1-4		

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	9	YEOH, T-S. "ESD Effects On Power Supply Clamps," Proceedings of the 6th International Symposium on Physical & Failure Analysis of Integrated Circuits (1997) pgs. 121-124	
	10	EDELSTEIN, D. et al. "Full Copper Wiring in a Sub-0.25 pm CMOS ULSI Technology," Technical Digest IEEE International Electron Devices Meeting (1997) pgs. 773-776	
	11	VENKATESAN, S. et al. "A High Performance 1.8V, 0.20 pm CMOS Technology with Copper Metallization," Technical Digest IEEE International Electron Devices Meeting (1997) pgs. 769-772	
	12	JENEI, S. et al. "High Q Inductor Add-on Module in Thick Cu/SiLK™ single damascene," Proceedings from the IEEE International Interconnect Technology Conference (2001) pgs. 107-109	
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	16	BOHR, M. "The New Era of Scaling in an SoC World," International Solid-State Circuits Conference (2009) Presentation Slides 1-66	
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	19	KURD, N. et al. "Next Generation Intel® Micro-architecture (Nehalem) Clocking Architecture," Symposium on VLSI Circuits Digest of Technical Papers (2008) pgs. 62-63	
	20	MALONEY, T. et al. "Novel Clamp Circuits for IC Power Supply Protection," IEEE Transactions on Components, Packaging, and Manufacturing Technology, Part C, Vol. 19, No. 3 (07-1996) pgs. 150-161	

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	21	GEFFKEN, R. M. "An Overview of Polyimide Use in Integrated Circuits and Packaging," Proceedings of the Third International Symposium on Ultra Large Scale Integration Science and Technology (1991) pgs. 667-677	
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	25	LIN, M.S. et al. "A New System-on-a-Chip (SOC) Technology – High Q Post Passivation Inductors," Proceedings from the 53rd Electronic Components and Technology Conference (05-30-2003) pgs. 1503-1509	
	26	MEGIC CORP. "MEGIC way to system solutions through bumping and redistribution," (Brochure) (02-06-2004) pgs. 1-3	
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	28	LIN, M.S. et al. "A New IC Interconnection Scheme and Design Architecture for High Performance ICs at Very Low Fabrication Cost – Post Passivation Interconnection," Proceedings of the IEEE Custom Integrated Circuits Conference (09-24-2003) pgs. 533-536	

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